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**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: BASELMANS et al.

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Filing Date: July 16, 2001

Examiner: UNKNOWN

Group Art Unit: 2872

Date: December 31, 2002

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of

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U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
SPM	AR	6,074,787	06/2000	TAKEUCHI	TECHNOLOGY CENTER 2800	1	
	BR						
	CR						
	DR						
	ER						
	FR						
	GR						
	HR						
	IR						
	JR						
	KR						
	LR						
	MR						
	NR						

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract	Translation Readily Available
	OR					Enclosed	No
	PR						
	QR						
	RR						
	SR						
	TR						
	UR						
	VR						
	WR						

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

SPM	XR	Kroyan et al., "Effects of Sub-Resolution Assist Features on Depth of Focus and Uniformity of Contact Windows for 193 nm Lithography," <i>Part of the SPIE Conference on Optical Microlithography XII</i> , Santa Clara, CA, March 1999, vol. 3679, pt. 1-2, pp. 630-638.			
	YR				
	ZR				
	AAR				

Examiner

Mohamedalla

Date Considered:

11/3/03

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.